

**SLOVENSKI STANDARD**  
**oSIST prEN IEC 60749-22-1:2025**  
**01-februar-2025**

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**Polprevodniški elementi - Metode za mehansko in klimatsko preskušanje - 22-1.**  
**del: Moč vezi - Preskusne metode za vlečenje žične vezi**

Semiconductor devices - Mechanical and climatic test methods - Part 22-1: Bond strength - Wire bond pull test methods

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**ICS:**

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TITLE:
<b>Semiconductor devices - Mechanical and climatic test methods - Part 22-1: Bond strength - wire bond pull test methods</b>

PROPOSED STABILITY DATE: 2031
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NOTE FROM TC/SC OFFICERS:
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## 69 INTERNATIONAL ELECTROTECHNICAL COMMISSION

70  
71  
72 SEMICONDUCTOR DEVICES –  
73 MECHANICAL AND CLIMATIC TEST METHODS –  
74

## 75 Part 22-1: Bond strength - wire bond pull test methods

76  
77 FOREWORD

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112 This first edition together with the first edition of IEC 60749-22-2, cancels and replaces IEC  
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114 permission of the copyright holder, JEDEC Solid State Technology Association.

115 This edition includes the following significant technical changes with respect to the previous  
116 edition:

117 Major update, including new techniques and use of new materials (e.g. copper wire) involving  
118 a complete rewrite as two separate subparts (this document and IEC 60749-22-2)

119 The text of this International Standard is based on the following documents:

XX/XX/FDIS	XX/XX/RVD
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120  
121 Full information on the voting for its approval can be found in the report on voting indicated in  
122 the above table.

123 The language used for the development of this International Standard is English

124 This document was drafted in accordance with ISO/IEC Directives, Part 2, and developed in  
125 accordance with ISO/IEC Directives, Part 1 and ISO/IEC Directives, IEC Supplement, available  
126 at [www.iec.ch/members\\_experts/refdocs](http://www.iec.ch/members_experts/refdocs). The main document types developed by IEC are  
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132 • withdrawn,  
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## SEMICONDUCTOR DEVICES – MECHANICAL AND CLIMATIC TEST METHODS –

### PART 22-1: BOND STRENGTH - WIRE BOND PULL TEST METHODS

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#### 1 Scope

This test method provides a means for determining the strength and failure mode of a wire bonded to, and the corresponding interconnects on, a die or package bonding surface and may be performed on unencapsulated or decapsulated devices. This test method may be performed on gold alloy, copper alloy, and silver alloy thermosonic (ball and stitch) bonds made of wire ranging in diameter from 15 µm to 76 µm (0,000 6" to 0,003"); and on gold alloy, copper alloy, and aluminium alloy ultrasonic (wedge) bonds made of wire ranging in diameter from 18 µm to 600 µm (0,000 7" to 0,024")

This wire bond pull test method is destructive. It is appropriate for use in process development, process control, and/or quality assurance.

This test method allows for two distinct methods of pulling wires:

- 1) One method incorporates the use of a hook that is placed under the wire and is then pulled.
- 2) One method requires that after the wire be cut, a clamp is placed on the wire connected to the bond to be tested, and this clamp is used to pull the wire.

This test method defines three pull tests. The Wire Pull Test (WPT) is appropriate for all bonded wires. The Ball Pull Test (BPT) and Stitch Pull Test (SPT) are appropriate for thermosonically bonded wires.

This test method can also be used on the following four applications of thermosonic and ultrasonic bonds, though each requires special considerations when performing the test method:

- a) Pulling aluminium wires and aluminium ribbons that are bonded with multiple ultrasonic bonds. See 5.3.2.2 for special considerations. Multiloop wires and ribbons are used in some high-power device packages.
- b) Pulling wires of reverse bonds which are also known as "stitch on ball". These types of bonds can include gold stitch on gold ball, copper stitch on copper ball, and copper stitch on gold ball. See Clause A.1 in Annex A for additional information.
- c) Pulling a thermosonically bonded wire that has a security bond (see 3.9) or security loop (see 3.19) placed on top of the stitch bond (see 3.3) in order to provide additional strength. See Clause A.2 for additional information.
- d) Pulling thermosonic wire bonds on stacked die when wires and/or bonds are not accessible to allow for proper pull testing. See 5.3.2.4 for special considerations

This test method does not include bond strength testing using wire bond shear testing. Wire bond shear testing is described in IEC 60749-22-2, Bond strength testing – Wire bond shear test methods.

#### 2 Normative references

The following documents are referred to in the text in such a way that some or all of their content constitutes requirements of this document. For dated references, only the edition cited applies.

181 IEC 60749-22-2, *Semiconductor devices – Mechanical and climatic test methods – Part 22-2:*  
 182 *Bond strength testing – Wire bond shear test methods.*

183 For undated references, the latest edition of the referenced document (including any  
 184 amendments) applies.

185 Also see Bibliography (informative) references.

186 **3 Terms and definitions**

187 For the purposes of this document, the following terms and definitions apply.

188 ISO and IEC maintain terminology databases for use in standardization at the following  
 189 addresses:

- 190 • IEC Electropedia: available at <https://www.electropedia.org/>
- 191 • ISO Online browsing platform: available at <https://www.iso.org/obp>

192 **3.1**

193 **bond, wire**

194 adhesion or welding of a wire (typically gold, aluminium, copper, or silver) to a bonding surface  
 195 using a thermosonic or ultrasonic wire bonding process.

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201 Note 1 to entry: The ball bond includes the enlarged spherical or nail-head portion of the wire that is provided by  
 202 the electronic flame-off, the underlying bonding pad, and the metallurgical weld interface between the ball bond and  
 203 the bonding pad.

204 **3.3**

205 **stitch bond**

206 second bond during the thermosonic (ball) bonding process, in which the wire is typically  
 207 bonded to the package bonding surface (e.g., leadframe, substrate, post, etc.).

208 Note 1 to entry: A stitch bond may also be referred to as a crescent bond

209 Note 2 to entry: For some unique constructions (e.g., reverse bond), the second bond may be formed on top of a  
 210 bump. See also “reverse bond” and “bump”).

211 **3.4**

212 **wedge bond**

213 attachment of a wire (typically aluminium, copper, or gold) or an aluminium ribbon to a die  
 214 bonding surface (typically aluminium pad metallization) or the package bonding surface (usually  
 215 a plated leadframe post or finger) using an ultrasonic bonding process.

216 **3.5**

217 **bonding surface**

218 surface to which the wire is bonded, which may be any one of the following: 1) the die pad  
 219 metallization or die surface metallization (e.g., MOSFET), 2) the package surface metallization  
 220 (e.g., leadframe, substrate, post), 3) a bump (see also “reverse bond” and “bump”), or 4) a  
 221 bonded stitch on die pad/flag or package surface metallization (see also “security bond” and  
 222 “security loop”).

223 **3.6**  
224 **bonding process, thermosonic**  
225 bonding process in which two members are joined through the combined application of heat,  
226 pressure, and an ultrasonic oscillatory lateral motion.

227 **3.7**  
228 **bonding process, ultrasonic**  
229 bonding process in which two members are joined through the combined application of pressure  
230 and an ultrasonic oscillatory lateral motion.

231 **3.8**  
232 **bonding wire**  
233 wire that is bonded to a chip bonding surface in order to electrically connect the chip to any  
234 other point within the device package.

235 **3.9**  
236 **ribbon (wire)**  
237 flat wire (non-round).

238 Note 1 to entry: Throughout this test method the term "wire" covers both wire and ribbon (wire).

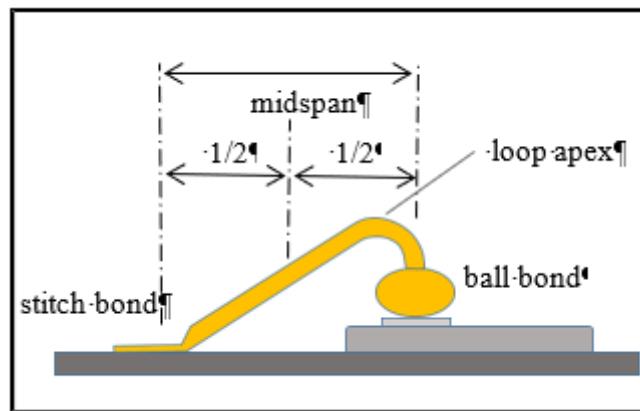
239 **3.10**  
240 **aluminium wire**  
241 aluminium alloy wire in which the aluminium content is typically 98 % or greater.

242 **3.11**  
243 **copper wire** (https://standards.iteh.ai)  
244 copper alloy wire in which the copper content is typically 99 %, but also includes copper wire  
245 with a very thin coating of palladium or gold and palladium.

246 **3.12**  
247 **gold wire**  
248 gold alloy wire in which the gold content is typically 99 % or greater.

249 **3.13**  
250 **silver wire**  
251 silver alloy wire in which the silver content is typically greater than 85 % for integrated circuits  
252 (ICs) and greater than 75 % for light emitting diodes (LEDs).

253 **3.14**  
254 **midspan**  
255 location on the bonded wire that is approximately one half of the horizontal distance between  
256 the two bonds. (See Figure 1)



257

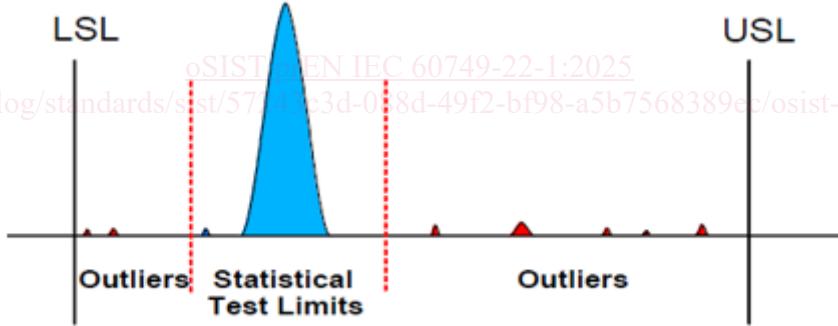
258 **Figure 1 – Definition of midspan**259 **3.15**260 **outlier product**

261 product that meets manufacturer specifications and user requirements but exhibits anomalous  
 262 characteristics with respect to a normal population (an example of which is depicted by the  
 263 histogram in Figure 2) and may be subject to a higher-than-normal level of failures in the user's  
 264 application.

265 Note 1 to entry: For purposes of this document, all Wire Bond Pull Tests have only a minimum pull value  
 266 requirement and no upper limit, thus the upper specification limit (USL) is not applicable.

267 Note 2 to entry: See also JESD50, "Special Requirements for Maverick Product Elimination and Outlier  
 268 Management".

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270 **Figure 2 – Depiction of eight outliers, seven of which are outlier products**271 **3.16**272 **reverse bond**

273 thermosonic bond for which the ball is placed on the package bonding surface and the stitch is  
 274 placed on a bump on the die. This is also known as "stitch on ball".

275 **3.17**276 **bump**

277 thermosonic ball bond from which the wire has been removed. It can be used as the underlying  
 278 ball bond for reverse bonds on which the stitch (2nd bond) for the reverse bond is placed, or  
 279 the ball bond placed on a stitch bond to form a security bond.

280 **3.18**281 **security bond**

282 placing of a bump (see also “bump”) on top of a stitch bond to improve the mechanical strength  
 283 of a stitch bond to withstand the shearing stress between the encapsulation material and the  
 284 bonding surface.

285 Note 1 to entry: Security bonds are commonly used in surface mount LED (light emitting diode) packages which  
 286 use non-filled encapsulants for the lens material that have higher coefficients of thermal expansion than silica filled  
 287 encapsulants, and thus exhort higher shear stresses on the stitch bond.

288 **3.19**289 **security loop**

290 security bond from which the wire has not been removed and the wire for the security loop is  
 291 attached to the same bonding surface as a stitch bond.

292 **3.20**293 **wire bond pull, destructive**

294 process in which an instrument pulls on a thermosonic or ultrasonic bonded wire until failure.

295 **3.21**296 **wire bond pull, non-destructive**

297 process in which an instrument pulls on a thermosonic or ultrasonic bonded wire with a specified  
 298 load that is below the minimum destructive pull value, such that no permanent damage or  
 299 degradation is expected to be imparted on the wire.

300 **3.22**301 **wire bond pull force (destructive)**

302 force required to cause any of the following to occur: the bonded wire to break; one of the bonds  
 303 to separate from a bonding surface; or one of the bonding surfaces to separate from the die,  
 304 leadframe, or substrate.

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305 **4 Apparatus and material**

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306 **4.1 Inspection equipment**

307 An optical microscope system or scanning electron microscope with a minimum of 70X  
 308 magnification is required to support the optical assessment of the resulting failure mode, such  
 309 as whether the wire break was ductile or brittle or if the bond lifted from pad or  
 310 leadframe/substrate with or without residues on pad or leadframe/substrate). However, a higher  
 311 magnification may be necessary for verifying Failure Codes 1, 2, 3, 6, 7, 8, and 9 (see 5.5 for  
 312 a detailed discussion of Failure Codes).

313 **4.2 Workholder**

314 The fixture used to hold the device, known as the “workholder” shall prevent any movement of  
 315 the device during wire bond pull testing and shall allow positioning the hook for optimum force  
 316 application to the wire.

317 **4.3 Wire bond pull equipment**

318 The apparatus shall consist of suitable equipment for applying a pulling force to the bonding  
 319 wire as required in accordance with this test method until failure occurs within the wire, wire  
 320 bond, or wire bonding surface. The equipment shall be capable of applying force at a constant  
 321 rate. The equipment shall indicate the applied force in SI and/or English units and be calibrated  
 322 over the full range of the expected values for the specific wire being pulled with an accuracy of  
 323  $\pm 5\%$  of the intended breaking load or  $\pm 2.9\text{ mN}$  ( $\pm 0.3\text{ gf}$ ), whichever is the greater tolerance.  
 324 The required range of force values will vary by wire material and wire cross-section.

325 The pull tester manufacturer's recommended pulling tool travel speed for the wire material being  
 326 tested should be used. To verify that the pull speed for a test was in an acceptable range, the  
 327 output of the loadcell shall be reviewed to ensure that the strain rate was consistent throughout  
 328 the test.

329 **4.4 Pulling hook**

330 The pulling hook should be made of a strong, rigid material that will not deform during pull  
 331 testing. The diameter of the wire used to make the hook utilized to apply force to the  
 332 interconnect wire shall be large enough and its final shape shall be such to ensure that the  
 333 force applied by the hook distributes the pull force through the wire to the bonds and does not  
 334 cut through the wire. Table 1 provides the minimum diameter for the pulling hook to ensure the  
 335 above requirement.

336 **Table 1 – Guidance for the minimum diameter of the pulling hook**

Wire diameter	Hook diameter
≤50 µm (0,002")	Minimum of 2,0x wire diameter
>50 µm (0,002") to ≤125 µm (0,005")	Minimum of 1,5x wire diameter
>125 µm (0,005")	Minimum of 1,0x wire diameter

337 For ribbon wire, use the equivalent round wire diameter which gives the same cross-sectional  
 338 area as the ribbon wire being tested. The flat portion of the hook (horizontal) should be > 1,25x  
 339 the equivalent diameter of the ribbon wire being tested.

340 The hook shall be smooth (no sharp edges) and free of defects and contamination which could  
 341 compromise the test results or damage the wire being pulled.

342 **4.5 Bond pull clamp** **Document Preview**

343 For the clamp pull tests, the clamp used shall be able to apply enough force to the wire being  
 344 pulled to hold it firmly such that it will not slip during the test. The clamp shall be large enough  
 345 to firmly hold the diameter of the wire or width and thickness of the ribbon to be pulled such  
 346 that it does not move when being pulled. The external shape and dimensions of the clamp shall  
 347 be optimized to allow for it to clamp onto the wire to be pulled, but also minimize the chance of  
 348 it touching and possibly damaging other wires on the device that are intended to be pull tested.

349 **5 Procedure**

350 **5.1 Calibration**

351 Before performing the wire bond pull test, it shall be determined that the equipment has been  
 352 calibrated in accordance with manufacturer's specifications and is presently in calibration.  
 353 Recalibration is required if the equipment is moved to another location.

354 **5.2 Visual examination of bonds to be tested after decapsulation**

355 **5.2.1 Applicability**

356 In addition to being a manufacturing process monitor, this test method can also be used to  
 357 assess bonds of encapsulated devices after soldering operations or after reliability stress  
 358 testing. To do this, the encapsulation material needs to be removed in a manner that does not  
 359 significantly degrade the wire, the bond, the bonding interface, or the bonding surface. Bond  
 360 pull force values are often lower for bonds that have been decapsulated, and therefore cannot  
 361 be compared to values for similar, unencapsulated bonds. If the decapsulation process is well  
 362 controlled and repeatable, which is the case for gold wire, then this test method can be used  
 363 for lot-to-lot comparison; however, it may be difficult to consistently control the decapsulation  
 364 process for copper and silver wires to ensure the accuracy of the results. For copper (Cu) and  
 365 silver (Ag) wires, the effectiveness of etch has been seen to vary due to the encapsulation

366 material and the level of reliability stress testing performed on the samples. See Annex B for  
 367 additional information regarding the decapsulation process of devices with Cu and Ag wire  
 368 bonds.

369 Bonds must also be examined to ensure that enough encapsulation material has been removed  
 370 to allow for suitable placement of the pull hook.

371 **5.2.2 Bond pad examination and acceptability criteria for both aluminium and copper  
 372 bond pad metallization**

373 If performing wire bond pull testing on a device which has been opened using wet chemical  
 374 and/or dry etch techniques, the bond pads shall be examined to initially ensure that there is no  
 375 absence of metallization on the bonding surface area due to chemical etching, and then ensure  
 376 that wire bonds are attached to the bonding surface. Bonds on aluminium or copper bond pads  
 377 with significant chemical attack or absence of metallization shall not be used for wire bond pull  
 378 testing.

379 It is possible that wire bonds on bonding surfaces without degradation from chemical attack  
 380 may not be attached to the bonding surface due to other causes (e.g., package stress),  
 381 however, in these cases wire bonds are considered valid and shall be included in the pull data  
 382 as a zero (0) pull force value.

383 **5.2.3 Examination and acceptability criteria for Cu and Ag wire and connections (all  
 384 bonds)**

385 When performing wire bond pull testing on a device with copper or silver wires, the connection  
 386 of the bond and wire shall be examined after decapsulation, both before or after the pull test to  
 387 ensure that there is no significant loss of metal or other damage due to decapsulation process  
 388 that might affect the results of the pull test. The pull result can be excluded for a copper bond  
 389 or a copper wire with significant chemical attack or other damage due to the decapsulation  
 390 process. Annex B provides additional information to assess what level of damage is acceptable.

391 **5.3 Performing the wire bond pull test**

392 **5.3.1 Wire bond pull test used**

393 Multiple wire bond pull tests are described in this document:

- 394 • wire pull (hook used to pull wire so that both bonds are stressed),
- 395 • ball pull (hook or clamp used to stress mainly the ball bond),
- 396 • stitch pull (hook or clamp used to stress mainly the stitch bond), and
- 397 • pull of wedge bonds (clamp or hook used to stress either one or both bonds).

398 Each of the pull tests and their variations are described below.

399 NOTE Not all bond pull tests give repeatable and/or reproducible results, as results may be affected by the geometry  
 400 of the device and the device decapsulation results (if decapsulation is required). The determination of which wires  
 401 and bonds are to be pulled within a device and by which pull test is determined by the qualification document that  
 402 references this test method and should ensure that the pulling of all types of bonds is adequately addressed.

403 **5.3.2 Hook pull method**

404 **5.3.2.1 Hook pull requirements and locations**

405 The wire bond pull equipment shall pass all self-diagnostic tests before beginning the test. The  
 406 wire bond pull equipment and test area shall be free of excessive vibration or movement.  
 407 Examine the pull hook to ensure that the correct hook is used and to verify it is in good condition